

Figure 1 Saturation plots of ALD Y_2O_3 films at a substrate temperature $200\text{ }^\circ\text{C}$ with $Y(\text{EtCp})_2(\text{iPr-amd})$ and (a) H_2O , (b) O_2 plasma and (c) H_2O plasma as reactant. The data determined by *in-situ* spectroscopic ellipsometry versus ALD cycle number.

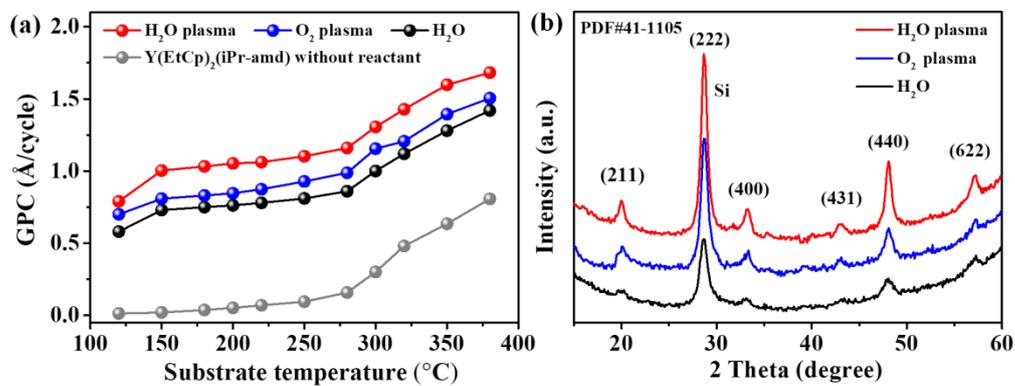


Figure 2 (a) GPC as a function of substrate temperature, (b) XRD patterns of Y_2O_3 films for $Y(\text{EtCp})_2(\text{iPr-amd})$ with H_2O , O_2 plasma, H_2O plasma.